

PATENT

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

**Present Application:**

Applicants : Vishnu K. Agarwal and  
Scott G. Meikle

Attorney Docket No. : 500453.04

Filed : Concurrently herewith

Title : POLISHING PADS AND PLANARIZING MACHINES FOR MECHANICAL  
OR CHEMICAL-MECHANICAL PLANARIZATION OF  
MICROELECTRONIC-DEVICE SUBSTRATE ASSEMBLIES, AND  
METHODS FOR MAKING AND USING SUCH PADS AND MACHINES

**Prior Application:**

Examiner : William P. Fletcher III

Art Unit : 1762

Serial No. : 09/621,021

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**PRELIMINARY AMENDMENT**

Box Patent Application  
Commissioner of Patents  
Washington, D.C. 20231

Sir:

Please amend the above-identified application as follows:

**In the Specification:**

Amend the specification by inserting a new section before the "Technical Field"  
as follows:

**-- CROSS-REFERENCE TO RELATED APPLICATIONS**

This application is a continuation of pending United States Patent Application  
No. 09/621,021, filed July 21, 2000, which is a divisional of United States Patent Application  
No. 09/201,576, filed November 30, 1998. --

In the Claims:

Please cancel claims 1-54, 58, 60-64, 65-68, 71, and 73-79.

Respectfully submitted,

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